

**EELE 414 – Introduction to VLSI Design**  
**Homework #2 due 10/22/15**

**Name:** \_\_\_\_\_  
**Grade:** \_\_\_\_\_ /10

1) MOS Behavior:  
(3 Points)

a) For a MOS structure with p-type Silicon, sketch the locations of the charge carriers during *depletion*. You can indicate electrons as  $e^-$  and holes as  $\oplus$ . Indicate the location of the depletion region and any polarization that occurs in the oxide. Indicate where  $x_d$  is located. Assume that  $V_B=0v$  and that  $V_G>0$  (small).

b) Now sketch the locations of the charge carriers during *inversion*. Show the depletion region, the inversion layer, and any polarization that occurs in the oxide. Indicate where  $x_{dm}$  is located. Assume that  $V_B=0v$  and that  $V_G>0$  (large).

c) If we dope the p-type silicon to a carrier concentration of  $N_A=10^{16}cm^{-3}$  and a resulting Fermi potential of  $\phi_{Fp}=-0.35 V$ , what is the maximum depletion depth ( $x_{dm}$ ) during inversion?

2) MOSFET Behavior  
(3 Points)

a) For a MOSFET structure with p-type Silicon, sketch the locations of the charge carriers during *depletion*. Indicate the location of the depletion region and any polarization that occurs in the oxide. Assume that  $V_B=V_S=V_D=0v$  and that  $V_G>0$  (small).

b) Now sketch the locations of the charge carriers during *inversion*. Show the depletion region, the inversion layer, and any polarization that occurs in the oxide. Assume that  $V_B=V_S=V_D=0v$  and that  $V_G>0$  (large).

c) When we apply a voltage to the Gate, it causes a depletion region beneath it. If  $V_S=V_D=0v$ , why is there a depletion region around the Source and Drain?

3) Threshold Voltage  
(3 Points)

- a) Given a MOSFET system with the following parameters:  
(2 points)

$$\begin{aligned}t_{\text{ox}} &= 200 \text{ \AA} \\ \phi_{\text{GC}} &= -0.245 \text{ V (Built in potential of the Gate-to-Channel MOS system)} \\ N_{\text{A}} &= 2 \cdot 10^{15} \text{ cm}^{-3} \\ Q_{\text{ox}} &= q \cdot 2 \cdot 10^{11} \text{ C/cm}^2\end{aligned}$$

Find the threshold voltage  $V_{\text{T0}}$  under zero substrate bias at room temperature ( $T=300 \text{ K}$ ). Note that  $\epsilon_{\text{ox}} = 3.97 \cdot \epsilon_0$  and  $\epsilon_{\text{Si}} = 11.7 \cdot \epsilon_0$ .

- b) Now assume that there is a substrate bias of  $V_{\text{SB}} = 0.5 \text{ V}$  and find the new threshold voltage ( $V_{\text{T}}$ ). You are given that  $\gamma=0.39 \text{ V}^{1/2}$ . Note: you will need some of your answer from part a ( $V_{\text{T0}}$  &  $\phi_{\text{F}}$ ). Hint, your answer from part (a) should have been between  $0.2 < V_{\text{T0}} < 0.4$ . If it isn't, use  $V_{\text{T0}}=0.3 \text{ v}$  for this part.  
(1 point)

4) MOSFET Modes of Operation  
(1 Point)

What regions are the following NMOS transistors operating in if  $V_{\text{T}}=1 \text{ v}$ ?

